Docket No.: <u>2328-050A</u> PATENT

Amendments to the Title and Specification:

Please amend the title as follows:

INDUCTIVE PLASMA PROCESSOR HAVING COIL WITH PLURAL WINDINGS
AND-METHOD OF CONTROLLING PLASMA DENSITY

Please delete the entire paragraph, after the title of "Technical Field" at page 1, lines 2-13 and replace it with:

RELATION TO CO-PENDING APPLICATION

This application is a divisional of US Patent Application No.: 09/821,027, filed March 31, 2001.

FIELD OF INVENTION

The present invention relates to an inductive plasma processor method wherein one winding of a coil is positioned relative to another winding of the coil for optimum workpiece processing.

Please amend the specification at page 9, lines 1-2 as follows:

improved vacuum plasma processor and method of operating same. wherein the plasma density incident on the work piece can be controlled at will.

Please delete paragraph 2 of page 9, in its entirety and replace it with:

An object of the present invention is to provide a new and improved vacuum plasma processor method wherein the plasma density incident on a workpiece has relatively high uniformity.

Please delete paragraphs 3 and 4 of page 9 in their entirety.

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Please rewrite the Summary of Invention as follows:

According to the invention, the plasma flux distribution on a workpiece of an inductive plasma processor is controlled. The processor includes having a center and axis and plural parallel connected windings adapted to be driven an excitation source. The plural parallel connected windings are concentric with the axis so an exterior winding of the coil surrounds the remainder of the coil. The method comprising positioning the exterior winding relative to the remainder of the coil so the plasma density incident on the workpiece has a predetermined desired relationship. The positioning step preferably includes turning the exterior winding and another winding of the coil relative to each other about the axis.

The above and still further objects, features and advantages of the present invention will become apparent upon consideration of the following detailed description.